

Patent Abstracts of Japan

PUBLICATION NUMBER : 11143047
PUBLICATION DATE : 28-05-99

APPLICATION DATE : 05-11-97
APPLICATION NUMBER : 09302904

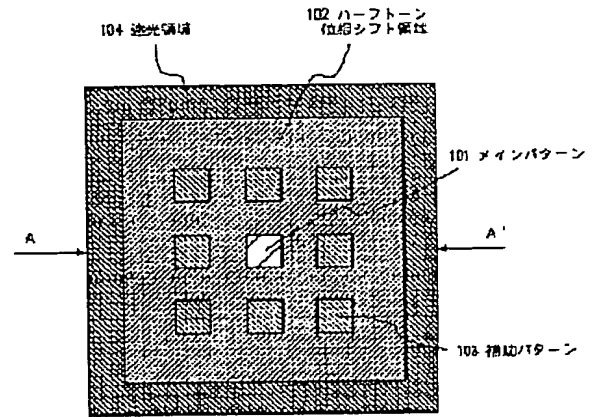
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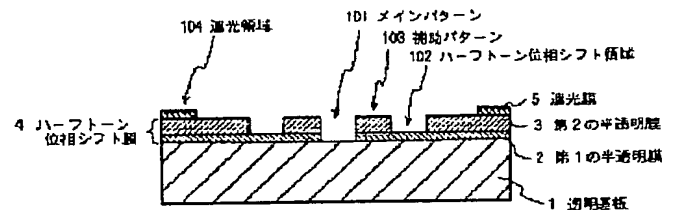
INT.CL. : G03F 1/08 H01L 21/027

TITLE : PHOTOMASK AND ITS PRODUCTION

(a)



(b)



ABSTRACT : PROBLEM TO BE SOLVED: To provide a photomask capable of improving the focusing characteristic of a translucent auxiliary pattern mask by a half-tone phase shift photomask and a process for producing the same.

SOLUTION: The half-tone phase shift mask arranged with the translucent auxiliary patterns 103 on the peripheries of a main pattern 101 is produced. The half-tone phase shift photomask is so set that a prescribed phase error (a deviation from 180° of a phase difference) occurs in the transmitted light of this photomask, by which the inclination of the focusing characteristic of the main pattern 101 by the translucent auxiliary patterns 103 is corrected.

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